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(74) Agents: **BERNADICOU, Michael, A.** et al.; Blakely,
Sokoloff, Taylor & Zafman LLP, 7th floor, 12400 Wilshire
Boulevard, Los Angeles, CA 90025 (US).

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(71) Applicant (for all designated States except US): **ASML
HOLDING N.V.** [NL/NL]; De Run 1110, NL-5503 LA
Veldhoven (NL).

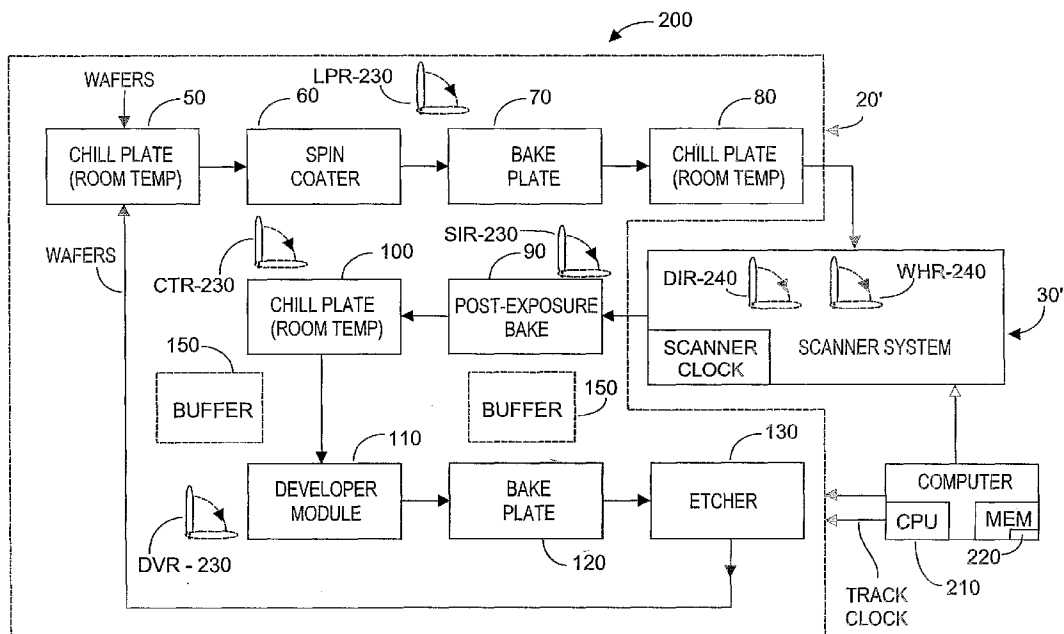
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(72) Inventor; and

(75) Inventor/Applicant (for US only): **OH, Hilario, L.**
[US/US]; 2899 Hastings Court, Rochester, MI 98306
(US).

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(54) Title: METHOD AND SYSTEM TO COMPENSATE FOR SCANNER SYSTEM TIMING VARIABILITY IN A SEMICON-
DUCTOR WAFER FABRICATION SYSTEM



(57) Abstract: A semiconductor wafer fabrication system that includes at least a track system and a scanner system compensates for deviations from nominal periodicity in the scanner system by dynamically introducing time delays when such deviations are detected. Preferably prior art static wait states are also introduced into the wafer recipe to reduce probability of resource conflicts. The resultant semiconductor wafer fabrication system can enjoy enhanced wafer throughput in that synchronization of wafer flow is maintained, despite such deviations.

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